



U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO.

212020US99

SERIAL NO.

09/911,444

APPLICANT

Tomasz KLOSOWIAK, et al.

FILING DATE

July 25, 2001

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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	3,802,967	04/09/74	Ladany et al.			
	AB	4,174,422	11/13/79	Matthews et al.			
	AC	4,404,265	09/13/83	Manasevit			
	AD	4,482,906	11/13/84	Hovel et al.			
	AE	4,523,211	06/11/85	Morimoto et al.			
	AF	4,661,176	04/28/87	Manasevit			
	AG	4,793,872	12/27/88	Meunier et al.			
	AH	4,846,926	07/11/89	Kay et al.			
	AJ	4,855,249	08/08/89	Akasaki et al.			
	AI	4,891,091	01/02/90	Shastri			
	AK	4,912,087	03/27/90	Aslam et al.			
	AL	4,928,154	05/22/90	Umeno et al.			
	AM	4,963,949	10/16/90	Wanlass et al.			
	AN	5,141,894	08/25/92	Bisaro et al.			
	AO	5,159,413	10/27/92	Calviello et al.			
	AP	5,173,474	12/22/92	Connell et al.			
	AQ	5,221,367	06/22/93	Chisholm et al.			
	AR	5,225,031	07/06/93	McKee et al.			
	AS	5,358,925	10/25/94	Neville Connell et al.			
	AT	5,393,352	02/28/95	Summerfelt			
	AU	5,418,216	05/23/95	Fork			
	AV	5,450,812	09/19/95	McKee et al.			
	AW	5,478,653	12/26/95	Guenzer			
	AX	5,482,003	01/09/96	McKee et al.			
	AY	5,514,484	05/07/96	Nashimoto			
	AZ	5,556,463	09/17/96	Guenzer			
	BA	5,588,995	12/31/96	Sheldon			
	BB	5,670,798	09/23/97	Schetzina			
	BC	5,733,641	03/31/98	Fork et al.			
	BD	5,735,949	04/07/98	Mantl et al.			
	BE	5,741,724	04/21/98	Ramdani et al.			
	BF	5,810,923	09/22/98	Yano et al.			
	BG	5,830,270	11/03/98	McKee et al.			
	BH	5,912,068	06/15/99	Jia			
	BI	6,020,222	02/01/00	Wollesen			
	BJ	6,045,626	04/04/00	Yano et al.			
	BK	6,064,078	05/16/00	Northrup et al.			
	BL	6,064,092	05/16/00	Park			
	BM	6,096,584	08/01/00	Ellis-Monaghan et al.			
	BN	6,103,008	08/15/00	McKee et al.			
	BO	6,136,666	10/24/00	So			
	BP	6,174,755	01/16/01	Manning			
	BQ	6,180,486	01/30/01	Leobandung et al.			

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	CA	3,766,370	10/16/73	Walther			
	CB	4,006,989	02/08/77	Andringa			
	CC	4,284,329	08/18/81	Smith et al.			
	CD	4,777,613	10/11/98	Shahan et al.			
	CE	4,802,182	01/31/89	Thornton et al.			
	CF	4,882,300	11/21/89	Inoue et al.			
	CG	4,896,194	01/23/90	Suzuki			
	CH	4,999,842	03/12/91	Huang et al.			
	CI	5,081,062	01/14/92	Vasudev et al.			
	CJ	5,155,658	10/13/92	Inam et al.			
	CK	5,248,564	09/28/93	Ramesh			
	CL	5,260,394	11/09/93	Tazaki et al.			
	CM	5,270,298	12/14/93	Ramesh			
	CN	5,286,985	02/15/94	Taddiken			
	CO	5,310,707	05/10/94	Oishi et al.			
	CP	5,326,721	07/05/94	Summerfelt			
	CQ	5,404,581	04/04/95	Honjo			
	CR	5,418,389	05/23/95	Watanabe			
	CS	5,436,759	07/25/95	Dijai et al.			
	CT	5,576,879	11/19/96	Nashimoto			
	CU	5,606,184	02/25/97	Abrokwah, et al.			
	CV	5,640,267	06/17/97	May et al.			
	CW	5,674,366	10/07/97	Hayashi et al.			
	CX	5,729,641	03/17/98	Chandonnet et al.			
	CY	5,790,583	08/04/98	Ho			
	CZ	5,825,799	10/20/98	Ho et al.			
	DA	5,857,049	01/05/99	Beranek et al.			
	DB	5,874,860	02/23/99	Brunel et al.			
	DC	5,926,496	07/20/99	Ho et al.			
	DD	5,937,285	08/10/99	Abrokwah, et al.			
	DE	5,981,400	11/09/99	Lo			
	DF	5,990,495	11/23/99	Ohba			
	DG	6,002,375	12/14/99	Corman et al.			
	DH	6,008,762	12/28/99	Nghiem			
	DI	6,055,179	04/25/00	Koganei et al.			
	DJ	6,107,653	08/22/00	Fitzgerald			
	DK	6,113,690	09/05/00	Yu et al.			
	DL	6,114,996	09/05/00	Nghiem			
	DM	6,121,642	09/19/00	Newns			
	DN	6,128,178	10/03/00	Newns			
	DO	6,143,072	11/07/00	McKee et al.			
	DP	6,184,144	02/06/01	Lo			
	DQ	6,222,654	04/24/01	Frigo			

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
1.2	EA	4,484,332	11/20/84	Hawrylo			
	EB	4,815,084	03/21/89	Scifres et al.			
	EC	4,876,219	10/24/89	Eshita et al.			
	ED	4,963,508	10/16/90	Umeno et al.			
	EE	5,060,031	10/22/91	Abrokwhah, et al.			
	EF	5,063,166	11/05/91	Mooney et al.			
	EG	5,116,461	05/26/92	Lebby et al.			
	EH	5,127,067	06/30/92	Delcoco et al.			
	EI	5,144,409	09/01/92	Ma			
	EJ	5,293,050	03/08/94	Chapple-Sokol et al			
	EK	5,356,831	10/18/94	Calviello et al.			
	EL	5,391,515	02/21/95	Kao et al.			
	EM	5,442,191	08/15/95	Ma			
	EN	5,444,016	08/22/95	Abrokwhah, et al.			
	EO	5,480,829	01/02/96	Abrokwhah, et al.			
	EP	5,528,414	06/18/96	Oakley			
	EQ	5,614,739	03/25/97	Abrokwhah et al.			
	ER	5,729,394	03/17/98	Sevier et al.			
	ES	5,731,220	03/24/98	Tsu et al.			
	ET	5,764,676	06/09/98	Paoli et al.			
	EU	5,777,762	07/07/98	Yamamoto			
	EV	5,778,018	07/07/98	Yoshikawa et al.			
	EW	5,778,116	07/07/98	Tomich			
	EX	5,801,105	09/01/98	Yano et al.			
	EY	5,828,080	10/27/98	Yano et al.			
	EZ	5,858,814	01/12/99	Goossen et al.			
	FA	5,861,966	01/19/99	Ortel			
	FB	5,883,996	03/16/99	Knapp et al.			
	FC	5,995,359	11/30/99	Klee et al.			
	FD	6,058,131	05/02/00	Pan			
	FE	6,137,603	10/24/00	Henmi			
	FF	6,146,906	11/14/00	Inoue et al.			
	FG	6,173,474	01/16/01	Conrad			
	FH	6,180,252	01/30/01	Farrell et al.			
	FI	4,242,595	12/30/0	Lehovec			
	FJ	4,398,342	08/16/83	Pitt et al.			
	FK	4,424,589	01/03/84	Thomas et al.			
	FL	4,876,208	10/24/89	Gustafson et al.			
	FM	4,482,422	11/84	McGinn et al.			
	FN	4,667,088	05/19/87	Kramer			
	FO	4,772,929	09/20/88	Manchester et al.			
	FP	4,841,775	06/27/89	Ikeda et al.			
	FQ	4,845,044	07/04/89	Ariyoshi et al.			

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INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	GA	4,868,376	09/19/89	Lessin et al.			
	GB	4,885,376	12/05/89	Verkade			
	GC	4,888,202	12/89	Murakami et al.			
	GD	4,891,091	12/90	Wanlass et al.			
	GE	5,051,790	09/24/91	Hammer			
	GF	5,055,445	10/08/91	Belt et al.			
	GG	5,081,519	11/14/92	Nishimura et al.			
	GH	5,143,854	09/01/92	Pirrung et al.			
	GI	5,185,589	02/09/93	Krishnaswamy et al.			
	GJ	5,191,625	03/02/93	Gustavsson			
	GK	5,194,397	03/16/93	Cook et al.			
	GL	5,208,182	05/04/93	Narayan et al.			
	GM	5,216,729	06/01/93	Berger et al.			
	GN	5,314,547	05/24/94	Heremans et al.			
	GO	5,352,926	10/04/94	Andrews			
	GP	5,356,509	10/18/94	Terranova et al.			
	GQ	5,371,734	12/06/94	Fischer			
	GR	5,372,992	12/94	Itozaki et al.			
	GS	5,405,802	04/11/95	Yamagata et al.			
	GT	5,442,561	08/15/95	Yoshizawa et al.			
	GU	5,453,727	09/26/95	Shibasaki et al.			
	GV	5,466,631	11/14/95	Ichikawa et al.			
	GW	5,473,047	12/05/95	Shi			
	GX	5,473,171	12/95	Summerfelt			
	GY	5,479,033	12/26/95	Baca et al.			
	GZ	5,486,406	01/23/96	Shi			
	HA	5,491,461	02/13/96	Partin et al.			
	HB	5,492,859	02/20/96	Sakaguchi et al.			
	HC	5,494,711	02/27/96	Takeda et al.			
	HD	5,504,035	04/02/96	Rostoker et al.			
	HE	5,504,183	04/02/96	Shi			
	HF	5,511,238	04/23/96	Bayraktaroglu			
	HG	5,512,773	04/96	Wolf et al.			
	HH	5,515,047	05/07/96	Yamakido et al.			
	HI	5,515,810	05/14/96	Yamashita et al.			
	HJ	5,519,235	05/96	Ramesh			
	HK	5,549,977	08/96	Jin et al.			
	HL	5,551,238	09/03/96	Prueitt			
	HM	5,552,547	09/03/96	Shi			
	HN	5,589,284	12/31/96	Summerfelt et al.			
	HO	5,602,418	02/11/97	Imai et al.			
	HP	5,633,724	05/27/97	King et al.			

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IA	5,650,646	07/22/97	Summerfelt			
IB	5,656,382	08/12/97	Nashimoto			
II	5,659,180	08/19/97	Shen et al.			
ID	5,661,112	08/26/97	Hatta et al.			
IE	5,679,965	11/95	Schetzina			
IP	5,725,641	08/10/98	MacLeod			
II	5,745,631	04/28/98	Reinker			
II	5,776,621	07/07/98	Nashimoto			
II	5,777,350	07/07/98	Nakamura et al.			
II	5,789,845	08/04/98	Wadaka et al.			
IK	5,792,569	08/11/98	Sun et al.			
IE	5,792,679	08/18/98	Nakato			
IM	5,796,648	08/18/98	Kawakubo et al.			
IN	5,801,072	09/01/98	Barber			
ID	5,812,272	09/22/98	King et al.			
IP	5,814,583	09/98	Itozaki et al.			
ID	5,825,055	10/20/98	Summerfelt			
IP	5,827,755	10/20/98	Yonchara et al.			
IS	5,833,603	11/10/98	Kovacs et al.			
IT	5,838,035	11/17/98	Ramesh			
IU	5,844,260	12/08/98	Ohori			
IV	5,846,846	12/08/98	Suh et al.			
IW	5,863,326	01/26/99	Nause et al.			
IX	5,872,493	02/16/99	Ella			
IX	5,879,956	03/99	Seon et al.			
IZ	5,880,452	03/09/99	Plesko			
JA	5,883,564	08/18/99	Partin			
JB	5,907,792	05/25/99	Droopad et al.			
JC	5,937,274	08/10/99	Kondow et al.			
JD	5,948,161	09/07/99	Kizuki			
JL	5,959,879	09/28/99	Koo			
JL	5,966,323	10/99	Chen et al.			
JG	5,987,011	11/18/99	Toh			
JH	6,022,410	02/08/00	Fraden et al.			
JL	6,022,410	02/08/00	Yu et al.			
JJ	6,023,082	02/08/00	McKee et al.			
JL	6,028,853	02/22/00	Haartsen			
JL	6,049,702	04/11/00	Tham et al.			
JM	6,078,717	06/20/00	Nashimoto et al			
JN	6,088,216	07/00	Laibowitz et al.			
JO	6,090,659	7/00	Laibowitz et al.			
JP	6,107,721	08/22/00	Lakin			
JQ	6,153,010	11/28/00	Kiyoku et al			

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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
KA	6,153,454	11/28/00	Krivokapic			
KB	6,191,011	02/01	Gilboa et al.			
KC	6,204,737	03/20/01	Ella			
KD	6,224,669	05/01/01	Yi et al.			
KE	6,225,051	05/01/01	Sugiyama et al.			
KF	6,241,821	06/05/01	Yu et al.			
KG	6,265,749	07/24/01	Gardner et al.			
KH	6,313,486	11/01	Kencke et al.			
KI	6,316,832	11/13/01	Tsuzuki et al.			
KJ	2002/0008234	01/02	Emrick			
KK	3,670,213	06/13/72	Nakawaga et al.			
KL	4,756,007	07/05/88	Qureshi et al.			
KM	4,773,063	09/20/88	Hunsperger et al.			
KN	5,394,489	02/28/95	Koch			
KO	5,406,202	04/11/95	Mehrgardt et al.			
KP	5,528,067	06/18/96	Farb et al.			
KQ	5,572,052	11/05/96	Kashihara et al.			
KR	5,767,543	06/16/98	Ooms et al.			
KS	6,175,497	01/16/01	Tseng et al.			
KT	6,197,503	03/06/01	Vo-Dinh et al.			
KU	6,248,459	06/19/01	Wang et al.			
KV	6,252,261	06/26/01	Usui et al.			
KW	6,255,198	07/03/01	Linthicum et al.			
KX	6,268,269	07/31/01	Lee et al.			
KY	6,291,319	09/18/01	Yu et al.			
KZ	6,316,785	11/13/01	Nunoue et al.			
LA	6,343,171	01/29/02	Yoshimura et al.			
LB	4,965,649	10/23/90	Zanio et al.			
LC	6,253,649	05/01	Kawahara et al.			
LD	6,211,096	04/01	Allman et al.			
LE	6,239,449	05/29/01	Fafard et al.			
LF	2001/0013313	08/16/01	Droopad et al.			
LG	6,184,044	02/06/01	Sone et al.			
LH	6,011,646	01/04/00	Mirkarimi et al.			
LI	5,227,196	07/13/93	Itoh			
LJ	6,150,239	11/21/00	Goesele et al.			
LK	5,441,577	08/15/95	Sasaki et al.			
LL	4,459,325	07/10/84	Nozawa et al.			
LM	4,392,297	07/12/83	Little			
LN	4,289,920	09/15/81	Hovel			
LO	5,281,834	01/25/94	Cambou et al.			
LP	4,901,133	02/13/90	Curran et al.			
LQ	5,514,904	05/07/96	Onga et al.			

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	MA	5,553,089	09/03/96	Seki et al.			
	MB	5,528,057	06/18/96	Yanagase et al.			
	MC	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			
	MH	5,073,981	12/17/91	Giles et al.			
	MI	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	Ho et al.			
	MK	6,362,017	03/26/02	Manabe et al.			
	ML	6,242,686	06/05/01	Kishimoto et al.			
	MM	5,689,123	11/18/97	Major et al.			
	MN	5,670,800	09/23/97	Nakao et al.			
	MO	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			
	MT	6,093,302	07/25/00	Montgomery			
	MU	6,372,813	04/16/02	Johnson et al.			
	MV	5,608,046	03/04/97	Cook et al.			
	MW	5,955,591	09/21/99	Imbach et al.			
	MX	6,022,963	02/08/00	McGall et al.			
	MY	6,083,697	07/04/00	Beecher et al.			
	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert			
	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			
	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina			
	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.			
	NJ	5,280,013	01/18/94	Newman et al.			
	NK	6,348,373 B1	02/19/02	Ma et al.			
	NL	6,339,664 B1	01/15/02	Farjady et al.			
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.			
	NP	6,011,641	01/04/00	Shin et al.			
	NQ	6,340,788 B1	01/22/02	King et al.			

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	OA 5,807,440	09/15/98	Kubota et al.			
	OB 4,681,982	07/21/87	Yoshida			
	OC 4,629,821	12/16/86	Bronstein-Bonte et al.			
	OD 4,452,720	06/05/84	Harada et al.			
	OE 3,935,031	01/27/76	Adler			
	OF 5,760,426	06/02/98	Marx et al.			
	OG 5,053,835	10/01/91	Horikawa et al.			
	OH 6,326,645 B1	12/04/01	Kadota			
	OI 5,770,887	06/23/98	Tadatomo et al.			
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QC	5,834,362	11/10/98	Miyagaki et al.			
QD	6,248,621 B1	06/19/01	Wilk et al.			
QE	5,266,355	11/30/93	Wernberg et al.			
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QK	5,103,494	04/07/92	Mozer			
QL	4,594,000	06/10/86	Falk et al.			
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QN	5,244,818	09/14/93	Jokers et al.			
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	UC	6,297,842 B1	10/02/01	Koizumi et al.			
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AAB	0 342 937	11/23/89	EP	X	
AAC	0 455 526	06/11/91	EP	X	
AAD	0 602 568	06/22/94	EP	X	
AAE	0 607 435	07/27/94	EP	X	
AAF	1 001 468	05/17/00	EP	X	
AAG	0 514 018	11/19/92	EP	X	
AAH	0 999 600	05/10/00	EP	X	
AAI	1 319 311	06/04/70	Great Britain	X	
AAJ	5-291299	11/05/93	Japan w/English Abstract	X	
AAK	11-238683	08/31/99	Japan	X	
AAL	11-260835	09/24/99	Japan w/English Abstract	X	
AAM	HEI 2-391	01/05/90	Japan w/English Abstract	X	
AAN	5-48072	02/26/93	Japan w/English Abstract	X	
AAO	52-88354	07/23/77	Japan w/English Abstract	X	
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AAR	61-108187	05/26/86	Japan w/English Abstract	X	
AAS	6-232126	08/19/94	Japan	X	
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AAU	63-34994	02/15/88	Japan w/English Abstract	X	
AAV	63-131104	06/03/88	Japan w/English Abstract	X	
AAW	63-198365	08/17/88	Japan w/English Abstract	X	
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ABO	3-41783	02/91	Japan (English Abstract only)		
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	BAB	2000-068466	03/00	Japan (Abstract)		
	BAC	64-50575	02/27/89	Japan		
	BAD	WO 98/05807	01/12/98	WIPO		
	BAE	WO 94/03908	02/17/94	WIPO		
	BAF	WO 01/33585	05/10/01	WIPO		
	BAG	1-102435	04/20/89	Japan w/English Abstract		
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	BAS	11340542	12/10/99	Japan (English Abstract)		
	BAT	WO 01/37330	05/25/01	WIPO		
	BAU	0 331 467	09/06/89	Europe		
	BAV	WO 00/16378	03/23/00	WIPO		
	BAW	0 926 739	06/30/99	Europe		
	BAX	0 964 453	12/15/99	Europe		
	BAY	5-152529	06/18/93	Japan w/English Abstract		
	BAZ	9-67193	03/11/97	Japan w/English Abstract		
	BBA	9-82913	03/28/97	Japan w/English Abstract		
	BBB	0 309 270	03/29/89	Europe		
	BBC	EP 0 957 522	11/17/99	Europe		
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	BBF	DE 100 17 137	10/26/00	GERMANY		
	BBG	WO 02 01648	01/03/02	WIPO		
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	BBM	0 538 611	04/28/93	Europe		
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CAC WO 02/03113	01/10/02	WIPO	
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CAE 0 630 057	12/21/94	EUROPE	
CAF 61-36981	02/21/86	Japan w/English Abstract	
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CAI EP 0 881 669	12/02/98	Europe	
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